



Effects of deposition temperature and *in-situ* annealing time on structure and magnetic properties of (001) orientation FePt films

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ABSTRACT

FePt films were prepared on (100) oriented single crystal MgO substrates at high temperature ranging from 620 until 800 °C and *in-situ* annealed for different times ranging from 0 to 60 min to obtain ordered FePt films. The structural analysis indicates that FePt films grow epitaxially on MgO (100) substrates. Both increasing deposition temperature and *in-situ* annealing time enhance the (001) texture and ordering of FePt films. The magnetic analysis shows that these L₁₀ FePt films have perpendicular anisotropy and the easy magnetization c-axis is perpendicular to the film plane. Magnetization reversal is controlled by a rotational mechanism. The hard magnetic properties of the films are improved with increasing deposition temperature or *in-situ* annealing time.

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1. Introduction

The FePt intermetallic alloy with L₁₀ ordered structure is considered as one of the leading candidate materials for the next generation of ultrahigh-density magnetic recording media because of its large magnetocrystalline anisotropy constant (7×10^7 erg/cm³), small grain size (about 3 nm) permitting thermal stability, high coercivity, and excellent corrosion resistance [1]. One of the key challenges of the application of FePt film with L₁₀ structure for perpendicular magnetic recording media is to control the c-axis texture of FePt films. Usually, FePt films deposited on glass or oxidized Si substrates tend to grow with random orientations or with (111) texture that place the c-axis of grains 37° out of the film plane [2,3]. For perpendicular recording application, the orientation of the L₁₀ FePt film should have the c-axis perpendicular to the film plane. Many efforts, such as the addition of TiN [4], Ag [5], CrRu [6], CrMo [7], and using RuAl underlayer [8] and nonepitaxial growth [9–13], have been devoted to promoting the L₁₀ FePt (001) texture as a perpendicular magnetic recording media.

It has also been demonstrated that epitaxial L₁₀ FePt films with perpendicular orientation of the easy magnetization the c-axis axis have been obtained by growth on single crystal MgO (100) substrates [14–16]. Because the lattice mismatch between L₁₀ FePt (001) and single crystal MgO (001) is about 8% and the lattice mismatch between Pt(001) and L₁₀ FePt (001) is 2%, a Pt

buffer layer is usually used to reduce the lattice mismatch between L₁₀ FePt films and single crystal MgO (100) substrates [17,18]. The thermal expansion coefficient of FePt is higher than that of single crystal MgO (100) substrates. The lattice mismatch between L₁₀ FePt (001) and single crystal MgO (001) could be reduced when the films are deposited at high temperature, which means that the deposition temperature can influence the structure and magnetic properties of L₁₀ FePt films directly deposited on single crystal MgO (100) substrates. In this work, we prepared L₁₀ FePt films with (001) texture on single crystal MgO (100) substrates and optimized the orientation of the films by controlling the deposition temperature, which could regulate the lattice mismatch between the substrates and the films. The effect of the *in-situ* annealing time on structure and magnetic properties of (001) orientation FePt films also was studied.

2. Experiments

FePt films with nominal thickness of 5 nm were prepared on (100)-oriented single crystal MgO substrates in an AJA International sputtering system by dc-magnetron and rf-magnetron sputtering at high temperature, ranging from 620 to 800 °C. The base pressure of the deposition chamber was about 4.2×10^{-8} Torr and Ar gas was kept at a pressure of 5 mTorr during sputtering. Before each deposition, the substrate was heated to the deposition temperature for 30 min to prevent moisture and contamination. After each deposition, the sample was also *in-situ* annealed at deposition temperature for different times ranging from 0 to 60 min to get ordered FePt films.

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After cooling to room temperature, a 5 nm C layer was deposited on the surface of FePt films to exclude oxidation. The substrates were rotated during film deposition to obtain a uniform film.

The compositions were estimated to be about Fe₅₀Pt₅₀ from the sputtering rates of Fe and Pt, which were determined by X-ray reflectivity measurements of the film thickness. The crystal structures of the films were characterized by θ – 2θ X-ray diffraction (XRD) with Cu $K\alpha$ radiation. The magnetic properties were measured with a superconducting quantum interference device (SQUID) up to a maximum applied field of 70 kOe at room temperature.

3. Results and discussion

3.1. The effect of deposition temperature on structure and magnetic properties

XRD patterns of FePt films deposited at $T_d=620$ (a), 700 (b), and 800 °C (c) are shown in Fig. 1. The films were also *in-situ* annealed at the corresponding deposition temperature for 60 min. The diffraction peaks around at $2\theta=23.7^\circ$ and 48.6° originate from the (001) and (002) reflections of the L1₀ crystal structure with (002) a fundamental reflection and (001) a superstructure reflection. Unlabeled peaks in the XRD patterns are from MgO substrates. Only (00n) diffraction peaks are observed in the diffraction patterns, indicating all the FePt films have the (001) orientation and also confirming that the films grow epitaxially on the MgO substrates. The value of the order parameter S of L1₀ FePt phase is determined from $0.85 \times [I_{(001)}/I_{(002)}]^{0.5}$, where $I_{(001)}$ and $I_{(002)}$ denote the intensities of (001) and (002) diffraction peaks, respectively [19]. The experimental values for the ratio of the integrated intensities of (001) and (002) diffraction peaks, i.e., $I_{(001)}/I_{(002)}$ have been estimated to be 0.641, and 0.866 for the FePt films deposited at 620 and 800 °C, respectively. So the values of the ordering parameter S are calculated to be 0.680 and 0.791, which means that the ordering parameters increase with

increasing deposition temperature. A sufficient deposition temperature could promote the Fe and Pt atoms to diffuse during the growth of the film such that they can adopt the correct position in the L1₀ phase and obtain higher order parameters. It can also be seen that even though the deposition temperature was increased to 800 °C, the films are not still fully ordered. It has been demonstrated that the activation energy of chemical ordering for L1₀ phase increases with the decrease of the film thickness, and the ordering temperature rises significantly as the FePt thickness decreases [20]. For our case, the film with nominal thickness of 5 nm is rather thin, so it is hard to get fully ordered L1₀ phases, even at 800 °C. We also estimated the “perpendicular” grain sizes from the half-peak widths of (001) diffraction peaks, according to the Scherrer formula. The grain sizes along (001) direction are about 7.1, 7.7 and 8.3 nm for FePt films deposited at 620, 700 and 800 °C, respectively, which are larger than the nominal thickness of 5 nm. In this work, the volume of magnetic material in the films is estimated from the measured sputtering rates, and the nominal film thickness is 5 nm based on these rates. However, the high deposition temperature causes the Fe–Pt crystals to form islands [21], which causes the packing density to be below 100% and the grain sizes along (001) direction are higher than the nominal thickness of 5 nm.

To further evaluate the degree of misorientation of the films deposited at different temperature, XRD rocking curves for (001) diffraction peaks were measured, and the results are shown in Fig. 2. The rocking curves can be fitted by a Gaussian function, and the Gaussian half-peak widths ε for the films deposited at different temperature are less than 2.50° , which indicates that the films obtained in the present study are highly (001) oriented. It can be seen that the Gaussian half-peak widths for the films deposited at different temperature decrease with increasing deposition temperature, which means that increasing the deposition temperature could improve the (001) orientation of L1₀ phase. Because the lattice mismatch between L1₀ FePt (001) and single crystal MgO (100) is about 8% and the thermal expansion

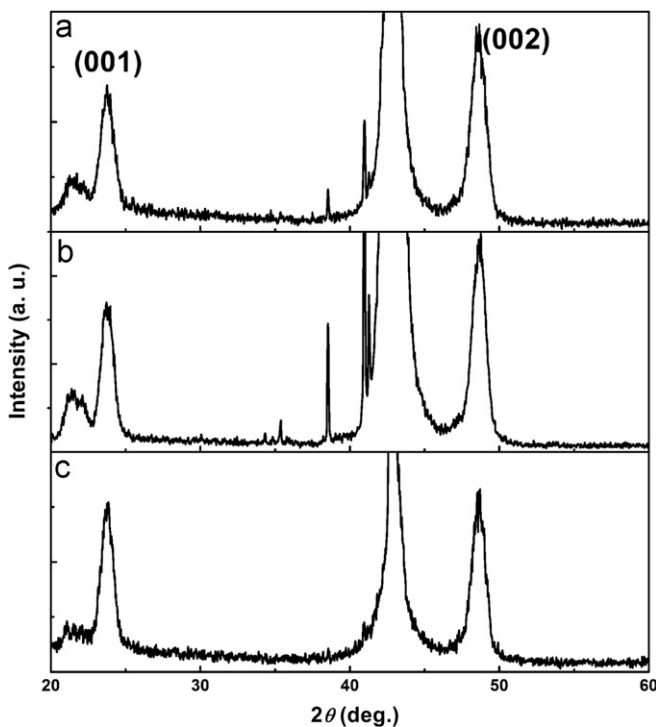


Fig. 1. XRD patterns of FePt films deposited at $T_d=620$ (a), 700 (b) and 800 °C (c).

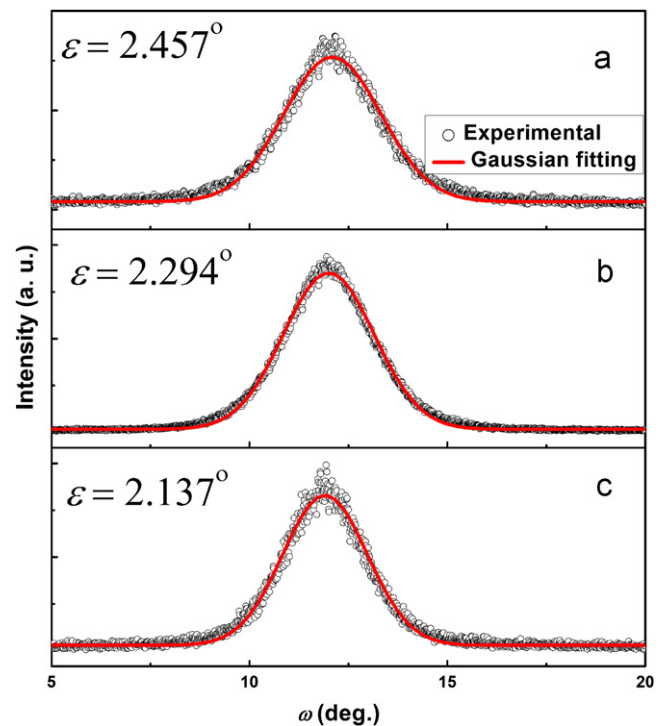


Fig. 2. XRD rocking curves for (001) diffraction peaks of FePt films deposited at $T_d=620$ (a), 700 (b) and 800 °C (c).

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